

Form PTO 1426
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LIST OF REFERENCES CITED BY APPLICANT

APPLICANT

Takuji MATSUMOTO, et al.

FILING DATE

January 12, 2004

GROUP

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
ah	AO	10-209167	08/07/1998	JAPAN (with English extract)		
	AP					
	AQ					
	AR					
	AS					
	AT					
	AU					
	AV					

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

ah	AW	Y. HIRANO, et al., IEEE International SOI Conference, pages 131-132, "BULK-LAYOUT-COMPATIBLE 0.18 μ m SOI-CMOS TECHNOLOGY USING BODY-FIXED PARTIAL TRENCH ISOLATION (PTI)", October 1999				
ah	AX	S. MAEDA, et al., Symposium on VLSI Technology Digest of Technical Papers, pages 154-155, "IMPACT OF 0.18 μ m SOI CMOS TECHNOLOGY USING HYBRID TRENCH ISOLATION WITH HIGH RESISTIVITY SUBSTRATE ON EMBEDDED RF/ANALOG APPLICATIONS", 2000				
ah	AY	Y. HIRANO, et al., IEEE, IEDM, pages 467-470, "IMPACT OF 0.10 μ m SOI CMOS WITH BODY-TIED HYBRID TRENCH ISOLATION STRUCTURE TO BREAK THROUGH THE SCALING CRISIS OF SILICON TECHNOLOGY", 2000				
ah	AZ	S. MAEDA, et al., Extended Abstracts of the 2001 International Conference on Solid State Devices and Materials, pages 270-271, "A HIGHLY RELIABLE 0.18 μ m SOI CMOS TECHNOLOGY FOR 3.3V/1.8V OPERATION USING HYBRID TRENCH ISOLATION AND DUAL GATE OXIDE", 2001				<input type="checkbox"/> Additional References sheet(s) attached

Examiner

Date

Considered

05/03/05

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.